

PATENT



F0601 (AMDP6)

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Date: 3-27-02

Himanshu S. Amin

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of:

Applicants: Arvind Halliyal

Serial No: 09/804,283

Filing Date: March 12, 2001

Examiner: Deven M. Collins

Art Unit: 2823

Title: **IN SITU MONITORING OF SHEET RESISTIVITY OF SILICIDES DURING RAPID THERMAL ANNEALING USING ELECTRICAL METHODS**

**Assistant Commissioner for Patents
U.S. Patent and Trademark Office
Washington, D.C. 20231**

REPLY TO RESTRICTION REQUIREMENT MAILED MARCH 18, 2002

This Reply is in response to the Restriction Requirement mailed on March 18, 2002 in connection with the above-identified patent application.

The Examiner requires restriction to one of the following two groups of claims:

(I) claims 20 to 23 or (II) claims 1-19 and 24-26.

Applicants hereby elect with traverse group II (claims 1-19 and 24-26 drawn to system for analyzing sheet resistivity) for further prosecution on the merits.


09/804,283

F0601(AMDP601US)

Should there be any questions regarding this paper, the Examiner is invited to contact applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,

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